

(12) International Application Status Report

Received at International Bureau: 12 May 2015 (12.05.2015)

Information valid as of: 26 November 2015 (26.11.2015)

Report generated on: 18 February 2020 (18.02.2020)

(10) Publication number:

WO2015/174677

(43) Publication date:

19 November 2015 (19.11.2015)

(26) Publication language:

Korean (KO)

(21) Application Number:

PCT/KR2015/004498

(22) Filing Date:

06 May 2015 (06.05.2015)

(25) Filing language:

Korean (KO)

(31) Priority number(s):

10-2014-0056381 (KR)

(31) Priority date(s):

12 May 2014 (12.05.2014)

(31) Priority status:

Priority document received (in compliance with PCT Rule 17.1)

(51) International Patent Classification:

G03F 7/20 (2006.01); **G02B 5/20** (2006.01); **G02F 1/13** (2006.01); **G06F 3/041** (2006.01)

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(54) Title (EN): LARGE-AREA PROXIMITY EXPOSURE DEVICE

(54) Title (FR): DISPOSITIF D'EXPOSITION DE PROXIMITÉ À GRANDE ÉTENDUE

(54) Title (KO): 대면적 근접 노광 장치

(57) Abstract:

(EN): The present invention relates to a large-area proximity exposure device, which improves precision of pattern transfer when proximity exposure is performed.

(FR): La présente invention concerne un dispositif d'exposition de proximité à grande étendue, qui permet d'améliorer la précision de transfert de motif lorsqu'une exposition de proximité est effectuée.

(KO): 본 발명은 근접 노광을 행할 때에 패턴의 전사 정밀도를 향상시키는 대면적 근접 노광 장치에 관한 것이다.

International search report:

Received at International Bureau: 24 July 2015 (24.07.2015) [KR]

International Report on Patentability (IPRP) Chapter II of the PCT:

Not available

(81) Designated States:

AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BN, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IR, IS, JP, KE, KG, KN, KP, KZ, LA, LC, LK, LR, LS, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PA, PE, PG, PH, PL, PT, QA, RO, RS, RU, RW, SA, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW

European Patent Office (EPO) : AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR

African Intellectual Property Organization (OAPI) : BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, KM, ML, MR, NE, SN, TD, TG

African Regional Intellectual Property Organization (ARIPO) : BW, GH, GM, KE, LR, LS, MW, MZ, NA, RW, SD, SL, ST, SZ, TZ, UG, ZM, ZW

Eurasian Patent Organization (EAPO) : AM, AZ, BY, KG, KZ, RU, TJ, TM

Declarations:

Declaration made as applicant's entitlement, as at the international filing date, to apply for and be granted a patent (Rules 4.17(ii) and 51bis.1(a)(ii)), in a case where the declaration under Rule 4.17(iv) is not appropriate